

SUBSTRATE HOLDING APPARATUS AND
SUBSTRATE POLISHING APPARATUS

ABSTRACT OF THE DISCLOSURE

A substrate holding apparatus comprises a substrate
5 holder body having a substrate holding side facing a
polishing surface and holding a substrate on the substrate
holding side and a retainer ring fixedly secured to the
substrate holder body. The retainer ring is arranged to
10 surround an outer periphery of the substrate held by the
substrate holder body so that the retainer ring engages
with the polishing surface radially outside the substrate
as the polishing of the substrate is effected. The
substrate holder body is provided with a membrane having
15 inside and outside surfaces. The inside surface cooperates
with a surface of the substrate holder body to define a
fluid pressure chamber to which a fluid pressure is applied.
The outer surface engages with the substrate held by the
substrate holder body.